

A Review on 7T SRAM

Surya Mishra¹, Himanshu Nautiyal²

Electronics & Communications, Sagar Institute of Research and Technology, Bhopal, Madhya Pradesh, India^{1,2}

suryamishrasdl@gmail.com¹, hnautiyal11@gmail.com²

Abstract: Today, low-power and high-speed SRAMs have become a distinct part of many VLSI chipsets. This is especially true for microchips, where chip sizes are developed on the chip with each age to expand the disparity in processor speed and cache speeds. SRAM is used as a cache, which is fast and is used to speed up processor allocation and memory interface. With modern technologies in VLSI innovation, logical port speeds have expanded their essence, but memory speed comparison has not been improved. Therefore, for PCs, SRAM memories are necessary to improve operating speed and DRAM is used as part of the main memory where density is more important than speed. In this work, we focused on the high-performance SRAM 6T system, which can be used as high-speed memory and low computer consumption.

Keywords: SRAM, 6T RAM, 7T RAM, DRAM, VLSI.

1. INTRODUCTION

In recent days, static RAM has become the most important part of the digital world. Because they occupy most SOC (system on chip). The device needs SRAM memory, mainly for the device to dissipate a small amount of power. But dynamic energy dissipation causes problems in digital circuits because dynamic energy depends on the voltage supply voltage, the switching frequency and the output voltage change. Dynamic power dissipation can be reduced by reducing voltage. At the same time, low voltage leads to performance degradation and also reduces the electrical voltage of the threshold, which in turn increases the secondary threshold current and thus increases the static energy dissipation. This article is about power dissipation of 6 transistors and 7 SRAM transistors. It also includes the functional display of SRAM 6T and 7T cells.

Memory is a basic element of a computer machine. Different types of SRAM cells are based on the type of load used in the elementary inverter of the flip-flop cell. There are currently three types of SRAM memory cells:

- The 4T cell (four NMOS transistors plus two poly load resistors)
- The 6T cell (six transistors — four NMOS transistors plus two PMOS transistors)

- The TFT cell (four NMOS transistors plus two loads called TFTs)

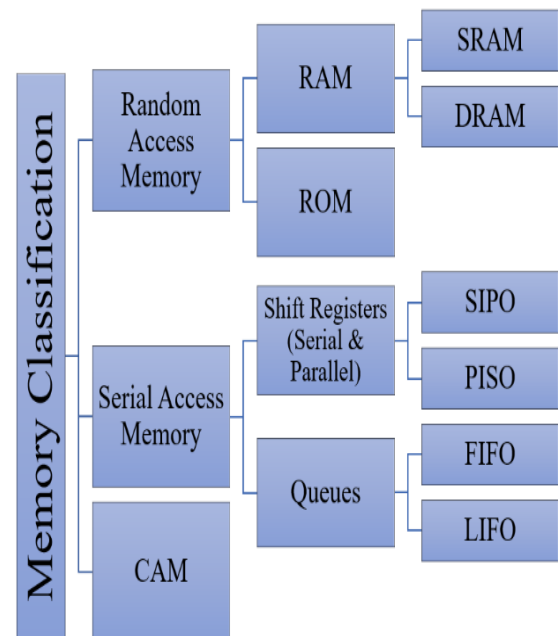


Figure 1: Classification of Memory

2. FEATURE COMPARISON BETWEEN MEMORY TYPES

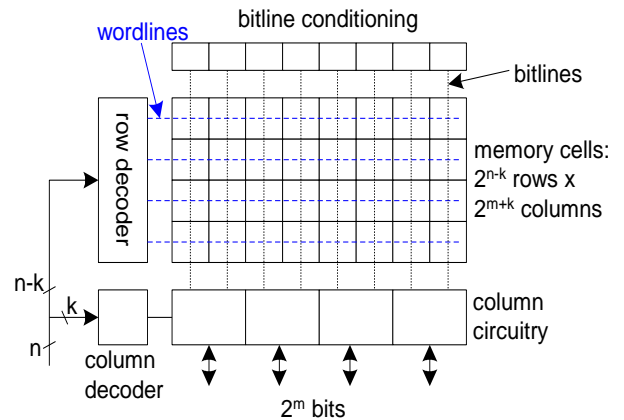
When you run a program within a computer, initially, the program must be loaded into the computer's core memory. Also, when not implemented, the program must remain loaded in the secondary memory of computers. This memory module functions as an additional block. In a program in memory, the entire process set that is made using the keyboard is written as a series of instructions. This set of instructions is called the program. In addition, data is entered in which the program should be run with the help of the keyboard and can be stored in memory. Memory can also store intermediate and final results. This design of the computer is the stored program where the program, data, and result are located in the memory of Von Neumann.

Properties	SRAM	DRAM	Flash
Speed	Very Fast	Fast	Very Slow
Density	Low	High	Very High
Endurance	Better	Batter	Poor
Power	Low	High	Very Low
Refresh	No	Yes	No
Retention	Volatile	Volatile	Non Volatile
Scalable	Good	Bad	Good
Mechanism	Bi-stable Latch	Capacitor	FN Tunneling HCL

Figure 2: Comparison between various memory

Array Architecture

Memory is created by using the array architecture. In this architecture 2^n words of 2^m bits each row where if $n \gg m$, fold by 2^k into fewer rows of more columns it have Good regularity which is easy to design. In this architecture have Very high density if good cells are used



The organization of the array, i.e. the composition of the memory cells to form the matrix, has gained more and more importance in Flash memories in comparison to EPROMs. The array of an EPROM memory is designed taking into account the access time that imposes some constraints to row and column length.

Memory - Real Organization

Designing ultra low power applications for energy-saving SRAM structures is very important. In the conventional form, the SRAM matrix contains more rows than the number of columns, but here [23] at a lower voltage, better energy efficiency can be achieved through a larger SRAM structure where the number of rows is less than the number of columns. Here we can get a 38% energy boost for the 8K SRAM matrix with the same electrical voltage. The minimum power can be used using a supply voltage equal to or less than the voltage value of the threshold. But the low value of the power supply voltage affects the stability of the design, i.e. the noise margin is reduced. Note that power consumption is reduced in non-square memory matrix structures, while minimum access time is achieved in the matrix architecture. Both dynamic and static power in the lines of words and bit lines are affected by the power supply voltage, meaning that power consumption decreases with low supply voltage. The limitations of a 6T SRAM cell are eliminated by an 8T cell that uses a separate port for the read operation. The word-line and bit-line capabilities determine the dynamic

energy value, while the memory density determines the leakage current responsible for static power dissipation. For higher power voltages, which is higher than 0.7 volts, the number of 128 rows is greater than the number of columns, ie 64 for fixed density 8KB. While the number of rows is gradually reduced with a set of power supplies

0.3 volts to 0.7 volts. In the 64K design, which consists of a total of 8 banks and each bank size is 8KB, the number of rows is reduced to 32 from 128.

3. SRAM MEMORY

SRAM or Static Random Access is a form of semiconductor memory that is widely used in electronics, microprocessors and general computing applications. This type of semiconductor memory gets its name from the fact that the data is stored there in a static way, and does not have to be dynamically updated as in the case of DRAM. Although the data in SRAM does not need to be dynamically updated, it is still volatile, which means that when power is removed from the memory device, the data is not retained and will disappear.

Static RAM (SRAM) is a type of volatile semiconductor memory to store parts of binary logic "1" and "0". SRAM uses installable closing circuits made of MOSFET transistors to store each bit. When you select a cell, the value to be typed in the cross-reference dump is stored. The primary SRAM cell consists of two cross-reflectors that are a simple blender as storage elements and two keys that bind these reflectors with complementary bit lines to connect with the extracellular.

SRAM memory applications

There are many different types of semiconductor memory available these days. You must make choices about the correct memory type for a particular application. Perhaps two of the most used types are DRAM and SRAM memory, which are used in processor and computer scenarios. Of these two SRAM is a little more expensive than the DRAM. However, SRAM is faster and consumes less power, especially when it is inactive. Also, this SRAM memory is easier to control than DRAM, because it is not necessary to take into account update cycles, as well as the way SRAM can be accessed is random access. Another advantage if SRAM is that it is more dense than DRAM.

4. 7T SRAM Cell

The SRAM 7T circuit is made up of two CMOS reflectors connected to each other by an additional NMOS transistor

connected to the read line and has NMOS transistors connected to the bit lines and line bar of the bits, respectively. Figure 2 shows the SRT 7T cell circuit, where the MN3 (WL) pass-through transistors are connected to the access writing procedure and the MN4 is connected to the read line (R) to perform read operations in the column bit lines (BL and BLB). Bit lines act as an I / O port that moves data from SRAM cells to a speaker to detect during the read process, or from writing to memory cells during write operations. All transistors have a minimum length ($L_{MIN} = 45$ nm depending on the technology used), while their offerings are usually design parameters. The value of WP1 and WP2 determines the width of the PMOS and WN1 transistors. WN2 is defined as the width of the NMOS controller transistors in the CMOS adapters, while WN3 and WN4 are the width of the access transistors.

5. LITERATURE SURVEY

Background / Objectives: In the modern era, due to the rapid development of many low-power VLSI circuits, key factors affecting circuit performance are of great importance. Static RAM (SRAM) is one of the important circuits used in low-power VLSI systems. Many researchers continue to focus on effective SRAM designs and increase the stability of SRAM cells. In general, single-line SRAMs are more robust than double-line SRAMs. The stability of SRAMs depends on certain factors, such as word line voltage control, leakage strength and power dissipation during the read / write process. Today, many low-power technologies have been developed to increase the stability of SRAM cells. One of these techniques is the non-conventional method called adiabatic technique or energy recovery. Applying this adiabatic technique to running the SRAM cell can improve the read noise margin, because it determines the stability of the SRAM cell. This adiabatic technology is primarily used in the way that adiabatic logic circuits consume less energy, conserves energy and re-uses the circuitry load. This document also proposes a new SRAM cell showing an improvement in the reading noise margin. Statistical methods / analysis: EDA rhythm tools were used in simulations. The designs of various SRAM cells are designed using the CMOS technology library of 180 nm and 45 nm. The output of the reading, writing, energy calculation and reading noise margin calculation is performed with the help of the Cadence Virtues tool. To calculate the reading noise margin, the input and output characteristics of the dual converter are plotted, and the maximum value of the square in the graph shows the value of the reading noise margin. In addition, comparisons of traditional SRAM cells are discussed with proposed

SRAMs in terms of power dissipation and noise reading range. Conclusion / Optimization: The results of the proposed SRAM cell are compared to the traditional SRAM cells. The total power consumption of the proposed SRAM is $1.061 \times 10^{-3} \text{ W}$ and the reading noise margin is 0.115. On the other hand, the conventional SRAM 6T cell consumes a total energy consumption of $1.033 \times 10^{-3} \text{ W}$ with the reading noise margin of 0.121. The power dissipation in the proposed circuit is reduced by 3.1% compared to the traditional SRAM 6T cell. In addition, the proposed SRAM cell structure has an improved noise margin of 52.17% compared to current technologies.

Because the memory technology in integrated systems (SoC) is reduced, embedded devices and embedded systems are emerging, so low power consumption is very necessary for VLSI system design. SRAM contains more than 70% of the SOC space. The standard 6T SRAM has two lines for read and write operations, so it consumes more power. There are many techniques to reduce power, such as VDD, Vtd, VDD, Vt, etc. The volume of stress negatively affects the stability of SRAM cells. In this document, a SRAM 7T double cell (seven transistors) was proposed and compared with a standard SRT 6T cell based on latency, write delay, leakage power consumption and SNM (during retention, read and write). This suggested cell uses a unique bit line for reading and writing. This also improves cell access time. The power consumption of leakage is reduced by 61.50%. The write delay is reduced by 66.67%. All simulations are done using the Eldo SPICE tool from Mentor Graphics with 65 nm technology at 27° C .

Increased demand for low-power mobile devices has increased the pressure on retractable hardware technology to operate on low-voltage voltages. But with the small size and low voltage supply advantage, the performance of SRAM, one important component of each device, degrades significantly. In this document, it was proposed cell SRAM 7T new, resulting in improved performance matrix fixed and dynamic when supply voltage up to 300 mV. The suggested bit cell contains one end end and a double-ended reading process. The proposed cell improves the readable noise margin and maintains a constant noise margin and write margin of 20%, 24% and 10%, respectively, compared to the conventional 7T bit structure. Compared to the traditional structure 6T, the proposed cell has improved by 76% in the noise margin of retaining a margin enhancer for writing by 26%. The cell does not read the traditional bit SRT less than 600 mV process 6T, while the proposed cell maintains a constant margin of noise of 47 mV voltage supply of 300 mV. The proposed cell is simulated for a 32 nm technical node.

In this work, a low power SRAM is suggested. In the suggested SRAM topology, additional circuits were added to a standard 6T-SRAM cell to improve performance. A seven (7T) transistor cell with a 45 nm CMOS function was proposed to achieve stability, power dissipation and performance improvements compared to previous designs for low-power memory operations. By optimizing the size and use of the proposed writing circuit layout, 45% energy savings are achieved in memory matrix operation compared to the traditional SRAM 6T design. The effect of process variations is examined in detail, and the CADENCE simulation shows that a 7T SRAM cell has excellent bearing capacity to handle variations..

In this document, a fully functional SRAM cell is designed for FinFET 7T to achieve greater conversion capability. For the reading process, P-type doors used for data analysis and transmission doors are used to write operations. In this, we use a 45 nm technique that provides up to 60.8% reduction in power supply with a greater reduction in power supply compared to other SRAM cells. The switching capacity is increased by the bitmap replaced by the NMOS stack and SRM 7T single-bit and NMOS stack that are designed and implemented in this document and therefore do not need to be loaded. Power RBL.

Technologies such as Internet of Things (IoT) represent new challenges for integrated circuit design, where it is desirable to have less power dissipation for mobile devices. Additional scalability of devices for portability requires reliable memories that can be operated at low voltage. In this document, a modified 7T SRAM cell has been proposed with a high constant. The proposed RAM 7T is compared with the traditional 6T SRAM and the LP7T SRAM in terms of static noise and power margins. SNM results show an increase of 48% and 78% with respect to the standard 6T for writing 0 and 1 respectively, up 122% in RSNM compared to the standard 6T SRAM bit cells and slightly better results than LP 7T for RSNM and SNM Hold when simulating pure cadence using technology CMOS 65nm. The proposed design uses 50% and 16.5% less power than the standard SRAM 6T for dynamic reading and writing, respectively. Monte Carlo simulation in the process and mismatch coefficients show a very small deviation..

6. CONCLUSION

This paper explains the basics of SRAM and its Classification. It seems to be that the 7T SRAM is very useful in this present scenario. This is required to minimize the power used of 7T SRAM. The literature Survey gives the

detail of various author who have tried to minimized the power consumption of 7T SRAM with various method.

REFERENCES

- [1] A. Manna and V. S. K. Bhaaskaran, "Improved read noise margin characteristics for single bit line SRAM cell using adiabatically operated word line," 2017 International Conference on Nextgen Electronic Technologies: Silicon to Software (ICNETS2), Chennai, 2017, pp. 385-393.
- [2] A. Q. Ansari and J. A. Ansari, "Design of 7T sram cell for low power applications," 2015 Annual IEEE India Conference (INDICON), New Delhi, 2015, pp. 1-4.
- [3] B. Rawat, K. Gupta and N. Goel, "Low Voltage 7T SRAM cell in 32nm CMOS Technology Node," 2018 International Conference on Computing, Power and Communication Technologies (GUCON), Greater Noida, Uttar Pradesh, India, 2018, pp. 238-241.
- [4] A. Jain and S. Sharma, "Optimization of Low Power 7T SRAM Cell in 45nm Technology," 2012 Second International Conference on Advanced Computing & Communication Technologies, Rohtak, Haryana, 2012, pp. 324-327.
- [5] G. Sneha, B. H. Krishna and C. A. Kumar, "Design of 7T FinFET based SRAM cell design for nanometer regime," 2017 International Conference on Inventive Systems and Control (ICISC), Coimbatore, 2017, pp. 1-4.
- [6] D. Sachan, H. Peta, K. S. Malik and M. Goswami, "Low power multi threshold 7T SRAM cell," 2016 IEEE 59th International Midwest Symposium on Circuits and Systems (MWSCAS), Abu Dhabi, 2016, pp. 1-4.
- [7] P. N. V. Kiran and N. Saxena, "Design and analysis of different types SRAM cell topologies," 2015 2nd International Conference on Electronics and Communication Systems (ICECS), Coimbatore, 2015, pp. 1060-1065.
- [8] K. F. Sharif, R. Islam, M. Haque, M. A. Keka and S. N. Biswas, "7T SRAM based memory cell," 2017 International Conference on Innovative Mechanisms for Industry Applications (ICIMIA), Bangalore, 2017, pp. 191-194.
- [9] G. Surekha, N. Balaji and Y. P. Sai, "Stability analysis of 7T-SRAM cell," 2016 10th International Conference on Intelligent Systems and Control (ISCO), Coimbatore, 2016, pp. 1-4.
- [10] C. B. Kushwah, S. K. Vishvakarma and D. Dwivedi, "Single-ended sub-threshold finfet 7T SRAM cell without boosted supply," 2014 IEEE International Conference on IC Design & Technology, Austin, TX, 2014, pp. 1-4.
- [11] K. F. Sharif, R. Islam and S. N. Biswas, "A New Model of High Speed 7T SRAM Cell," 2018 International Conference on Computer, Communication, Chemical, Material and Electronic Engineering (IC4ME2), Rajshahi, 2018, pp. 1-4.
- [12] C. S. H. Kumar and B. S. Kariyappa, "Analysis of low power 7T SRAM cell employing improved SVL (ISVL) technique," 2017 International Conference on Electrical, Electronics, Communication, Computer, and Optimization Techniques (ICECCOT), Mysuru, 2017, pp. 478-482.